

TSMC-02-130

January 5, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/692,030 10/23/03 |

Syun-Ming Jang et al.

IMPROVEMENT OF SiOC PROPERTIES AND
ITS UNIFORMITY IN BULK FOR DAMASCENE
APPLICATIONS

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on January 27, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

SB Ackerman 1/27/04

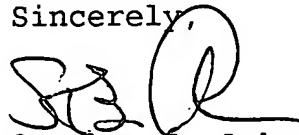
U.S. Patent 6,372,661 to Lin et al., "Method to Improve the Crack Resistance of CVD Low-K Dielectric Constant Material," describes SiOC films and post-treatments.

U.S. Patent 6,348,407 to Gupta et al., "Method to Improve Adhesion of Organic Dielectrics in Dual Damascene Interconnects," describes a plasma treatment of a low-k layer and an etch stop layer in a dual damascene process.

U.S. Patent 6,323,125 to Soo et al., "Simplified Dual Damascene Process Utilizing PPMSO as an Insulator Layer," describes a plasma treatment and PPMSO layer in a dual damascene process.

U.S. Patent 6,323,121 to Liu et al., "Fully Dry Post-Via-Etch Cleaning Method for a Damascene Process," describes a dual damascene process with etch stops and a plasma treatment.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', with a large circular flourish to the right.

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

Order Number (Optional)

Application Number

TSMC-02-130

10/692,030

Applicant:

Syun-Ming Jang et al.

Filing Date

10/23/03

Or you are not

INFORMATION DISCLOSURE CITATION
IN AN APPLICATION

(Use several sheets if necessary)

U. S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion, Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.